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| FORM PTO-1449 (MODIFIED) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT | ATTORNEY DOCKET NO. SP02-191 | SERIAL NO. |
| | APPLICANT Qiao Li, et al. | |
| | FILING DATE | GROUP: |

| REFERENCE DESIGNATION | | | | U.S. PATENT DOCUMENTS | | | |
|-----------------------|----|-----------------|---------|-----------------------|-------|-----------|------------------------|
| Examiner Initial | | Document Number | Date | Name | Class | Sub-Class | Filing Date if Approp. |
| (V) | AA | 6,562,126B2 | 5/13/03 | Price | 117 | 81 | |
| | AB | | | | | | |
| | AC | | | | | | |
| | AD | | | | | | |
| | AE | | | | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
|--------------------------|----|-----------------|------|---------|-------|-----------|--------------------|
| | | Document Number | Date | Country | Class | Sub-Class | Translation Yes No |
| | AL | | | | | | |
| | AM | | | | | | |
| | AN | | | | | | |
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| | AP | | | | | | |
| | AQ | | | | | | |

| OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.) | | |
|--|----|--|
| m) | AR | "Fundamentals of Solidification" W. Kurz, Trans Tech Publication 1986 pages 34-43 |
| | AS | "Phonon conduction in elastically anisotropic cubic crystals" A. K. McCurdy, Physical Review B, Vol. 26, Number 12, Dec. 15, 1982 |
| | AT | "Intrinsic birefringence in calcium fluoride and barium fluoride," J. H. Burnett, et al, Physical Review B, Vol. 64 241102(R) |
| | AU | "Progress Report: 157-nm lithography prepares to graduate," S. Dana, SPIE's OE Magazine February 2003 |
| m) | AV | "Intrinsic Birefringence in Crystalline Optical Materials: a New Concern for Lithography," J. H. Burnett, et al Future Fab International, Issue 12 |
| | AW | |

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609: draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.